

## CLAIMS

1. A Co-Cr-Pt-B alloy sputtering target comprising an island-shaped rolled structure formed from a Co-rich phase based on the primary crystal formed upon  
5 casting.
2. A Co-Cr-Pt-B alloy sputtering target according to claim 1, wherein the island-shaped rolled structure has an average size of  $200\ \mu\text{m}$  or less.
3. A Co-Cr-Pt-B alloy sputtering target according to claim 1 or claim 2,  
10 comprising a Co-rich phase and B-rich phase island structure based on the eutectic structure formed upon solidification between the island-shaped structures formed from a Co-rich phase based on the primary crystal.
4. A Co-Cr-Pt-B alloy sputtering target according to any one of claims 1 to 3,  
wherein the average crystal grain size of the crystal in the Co-rich phase is  $50\ \mu\text{m}$  or less.
- 15 5. A Co-Cr-Pt-B alloy sputtering target according to any one of claims 1 to 4,  
comprising a hot rolled structure.
6. A Co-Cr-Pt-B alloy sputtering target according to claim 5, wherein the hot rolling ratio is 15 to 40%.